What is claimed is:

1. A process for preparing halogen-containing silanes of the general formula (I):

5

10

20

25

30

 $R_a H_b SiX_c$ (I)

where

R is a substituted or unsubstituted alkyl or aryl radical having from 1 to 10 carbon atoms of which one or more may be replaced by $-CO_{-}$, $-CO_{2}_{-}$, $-O_{-}$, $-S_{-}$, $-SO_{-}$, $-SO_{2}_{-}$, $-NH_{-}$ or $-NR'_{-}$, where R' is a substituted or unsubstituted alkyl radical having from 1 to 20 carbon atoms,

15 X is fluorine, chlorine or bromine, a is an integer of 0, 1, 2 or 3, b is an integer of 0, 1, 2 or 3 and c is an integer of 1, 2, 3 or 4,

with the proviso that the sum of a + b + c = 4, characterized in that silicon, under the action of microwave energy, is reacted with mixtures of the elements or compounds selected from the group consisting of halogens halogens or organohalogen compounds or halogens and hydrogen or halogens and hydrogen halides or organohalogen compounds or organohalogen compounds and hydrogen or organohalogen compounds and hydrogen halide or hydrogen halides or fluorosilanes and hydrogen or fluorosilanes and hydrogen halide or hydrogencontaining chlorosilanes and hydrogen or hydrogencontaining chlorosilanes and hydrogen halides or organohalosilanes and hydrogen ororganohalosilanes and hydrogen halides or

hydrocarbons and hydrogen halides.

2. The process of claim 1, characterized in that silicon is contacted with a gas atmosphere of a halogen or of a halogen compound and exposed to microwave energy.

5

- 3. The process of claim 1 or 2, characterized in that crystalline, especially coarsely crystalline, silicon is used.
- 10 4. The process of claim 1 or 2, characterized in that amorphous silicon is used.
- The process of claim 4, characterized in that amorphous silicon is used in a mixture with
 crystalline silicon.
 - 6. The process of at least one of claims 1 to 5, characterized in that silicon is used in conjunction with a catalyst or promoter.

20

25

- 7. The process of at least one of claims 1 to 6, characterized in that silicon is used in conjunction with a substance which absorbs microwave energy and transfers thermal energy to silicon.
- 8. The process of at least one of claims 1 to 7, characterized in that hydrogen halide is used.
- 30 9. The process of at least one of claims 1 to 8, characterized in that the catalyst or promoter used is a metal or metal compound, especially Cu.
- 10. The process of at least one of claims 1 to 9, characterized in that nonpulsed microwave energy

5

15

is used.

- 11. The process of at least one of claims 1 to 10, characterized in that silicon having a particle size of $> 70 \mu m$ is used.
- 12. The process of at least one of claims 1 to 11, characterized in that the halogen compound used is an organohalogen compound, in particular alkyl or aryl halides, especially methyl chloride. 10
 - The process of at least one of claims 1 to 12, 13. characterized in that the silicon used is a silicon alloy, especially ferrosilicon.
- The process of claim 1, characterized in that 14. compounds of the F_nSiH_{4-n} type where n = 1-3 are prepared by contacting elemental silicon under microwave excitation with mixtures 20 fluorosilanes with hydrogen or hydrogen fluoride or hydrogen and hydrogen fluoride.
- 15. The process of claim 14, characterized in that compounds of the F_nSiH_{4-n} type where n = 1-3 are prepared by contacting elemental silicon under 25 microwave excitation with mixtures of SiF4 gas with hydrogen or hydrogen fluoride or hydrogen and hydrogen fluoride.
- The process of claim 1, characterized in that 30 16. compounds of the Cl_nSiH_{4-n} type where n = 1-3 are prepared by contacting elemental silicon under microwave excitation with mixtures of hydrogencontaining chlorosilanes with hydrogen or hydrogen 35 chloride or hydrogen and hydrogen chloride.

5

10

30

The process of at least one of claims 14 to 16, 17. characterized in that a mixture of different compounds of the X_nSiH_{4-n} type where X is fluorine or chlorine is prepared.

- 18 -

- The process of claim 17, characterized in that the 18. by low-temperature mixture is separated (condensation) or liquid distillation distillation.
- any of claims 18, of 14 19. The process characterized in that the degree of hydrogenation is regulated by varying the hydrogen or hydrogen 15 halide or the gas pressure of the hydrogen and halogen water hydrogen halide.
- The process of at least one of claims 14 to 19, 20. characterized in that the XMSiH_{4-n} compounds obtained where X is fluorine or chlorine are 20 decomposed pyrolytically to obtain highly pure silicon.
- The process of claim 20, characterized in that the 21. gases formed in the course of the pyrolytic 25 decomposition are recycled back into the system for the purposes of recycling or reused directly synthesize SiX4 where X is fluorine or chlorine.
 - The process of claim 1, characterized in that 22. elemental silicon is contacted under microwave excitation with mixtures of ·organohalogen compounds with hydrogen or hydrogen halide or

hydrogen and hydrogen halide.

23. The process of claim 1, characterized in that the hydrocarbon used is methane or ethane.